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4H-SiC p-i-n 紫外光电探测器的制备及其特性研究

Fabrication and Characterization of 4H-SiC p-i-n
Photodetectors

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摘 要

4H-SiC 材料具有优越的电学性能，用于低电平的紫外线检测时，还具有可见光盲、在太阳盲光谱区域量子效率较高、低漏电流、抗辐射和耐高温等优点，本文制备并详细研究了 4H-SiC p-i-n 紫外光电探测器的光电性能，取得了以下重要的结果：

1. 制备出高性能 4H-SiC p-i-n 紫外光电探测器，探测器的光敏面积为 $200 \times 200 \mu\text{m}^2$ ，封装在 TO-2 外壳上，用熔融石英玻璃作为光学窗口；

2. 研究了 4H-SiC p-i-n 紫外光电探测器电容-电压 (C-V) 特性。结果表明探测器在 0 偏压时的高频 (1MHz) 结电容约为 3.4pF 并基本不随偏压变化，表明器件在较低偏压时 i 型层已基本处于耗尽状态。变温低频 (100kHz) 的反向和正向 C-V 测量表明深能级缺陷会导致器件结电容增大并具有较强的电压依赖性。紫外线照射也会导致结电容增大，不同波长单色光照射时结电容的增大幅度相差较大，这些结果对于器件实际应用时的电路优化设计具有较大的参考价值；

3. 研究了 4H-SiC p-i-n 紫外光电探测器电流-电压 (I-V) 特性。测量结果显示室温时光电探测器的暗电流密度在 -5V 偏压时约为 $4.5 \text{nA} \cdot \text{cm}^{-2}$ ，主要来源于表面缺陷和材料位错导致的隧穿电流；击穿电压约 70V，来源于隧穿击穿。暗电流随温度升高而增大，击穿电压则正好相反。缺陷和位错是导致器件暗电流较大、击穿电压较低的主要原因；

4. 研究了 4H-SiC p-i-n 紫外光电探测器的光谱响应特性。室温时探测器的光谱响应度约为 0.13A/W 并且基本不随偏置电压变化，光电流-暗电流比值和紫外可见光抑制比分别大于 4 个和 3 个数量级，表明探测器具有较好的光电性能。变温测量表明响应度随温度升高而增大，但由于暗电流随温度增大的速度更快导致光电流-暗电流比值随温度升高而下降；不同波长的响应度具有不同的温度特性即短波长的温度依赖性更小、长波长则反之；温度较低时，量子效率随温度升高而增大，温度大于 250K 时，250nm 以下波长的量子效率基本不随温度变化，250nm 以上波长量子效率有二次增大现象，但增大的速度有所减缓。

关键词：4H-SiC；p-i-n 紫外光电探测器；光电特性

ABSTRACT

Silicon Carbide (SiC) has excellent physical, chemical and electronic properties. The ultraviolet (UV) photodetectors (PDs) based on 4H-SiC have the advantages of solar blindness to the background light, high quantum efficiency, low dark current, extremely radiation hardness, able to operate at high temperature and so on. In this dissertation, the high performance 4H-SiC p-i-n UV PDs has been fabricated and the electrical and photoelectric properties have been carried out and discussed as following:

1. The 4H-SiC p-i-n UV PDs with photo-sensitive area of $200 \times 200 \mu\text{m}^2$ have been fabricated. The chip was mounted on TO-2 metallic case and fused quartz glass was used as optical incidence window.

2. The capacitance-voltage properties of the PDs as a function of voltage, frequency, temperature as well as UV illumination have been carried out. The results show that the junction capacitance of the PD under 1MHz measured frequency and zero bias is about 3.4pF and almost independent of reverse bias, which indicated that the i-layer of the PD has been depleted at low reverse bias. Under 100kHz measured frequency, however, the junction capacitance was increased to about 9.6pF and linear decreased with reverse voltage increased. This frequency-dependent of junction capacitance imply that deep-level defect centers are presented within the PD and play a significant role on the junction capacitance and can be confirmed by the observed negative differential capacitance at forward bias condition under 100kHz frequency. The capacitances are increased with increasing reverse bias due to the thermal activation of the carriers captured by the deep-level centers as well as the increasing of the density of the intrinsic carriers. Under UV illumination, the capacitance exhibit wavelength-dependent property. That is, for the wavelengths below 230nm or above 360nm, the capacitances are almost both wavelength- and voltage-independent. As the wavelength above 235nm, the measured capacitance increases abruptly and then keeps nearly as a constant in the wavelength range 260-360nm. Finally the capacitance sharply decreases again. The observed wavelength dependence of the capacitances can be explained by the penetration depth of the illumination light. As the illumination wavelength is below 240nm, the incident photons penetrate within the p+ layer and most of photons are recombined with the existed surface states.

Consequently, the effective carrier concentrations and the capacitance do not increase much. As the excitation wavelengths above 240nm, the photo-generated carriers can be attracted into the space charge region and contribute to the capacitance.

3. The reverse- and forward-bias current-voltage (I-V) properties of the PDs as a function of temperature have been achieved. The room temperature dark current density of the PD is about $4.5 \text{ nA}\cdot\text{cm}^{-2}$ at 5V reverse-bias and originated from the surface defect and deep-level defect assistant tunneling current. The break voltage is about 70V due to the tunneling breakdown. The dark current is increased and the break voltage is decreased with increasing temperature. These results indicated the surface defects and deep-level defects play a primary role on the performance degradation of the PDs.

4. The responsivities have been obtained with wavelength from 200 to 400nm and temperature from 20-460K. The peak responsivity at room temperature is about 0.13A/W at 266nm and independent of bias voltage less than 20V. The ratio of photo-to dark-current and the rejection ratio (PDCR) of visible-to UV are high than 3 and 4 orders of magnitude, respectively. These results indicate that the fabricated PDs have excellent photoelectric properties. Moreover, the responsivity is increased but the PDCR is decreased with elevated temperature due to high the increasing rate of the dark current by comparing with that of photon current. The responsivities at long wavelength region ($>260\text{nm}$) exhibit strong temperature-dependence behaviors, whereas the short wavelength region ($<250\text{nm}$) do not. The quantum efficiency (QE) of the PD increases with temperature within 20-250K temperature range. As temperature further increasing, the QEs of the wavelength within 200-250nm show a saturation behavior and are independent of temperature. The QEs of the wavelength larger than 250nm still increase with temperature but the rate of increasing is slow down.

Key Words: 4H-SiC; p-i-n UV photodetector; Photoelectric

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第 1 章 绪论

§1.1 紫外线简介

§1.1.1 紫外线的分类

紫外线由德国物理学家里特 (J. W. Ritte) 于 1801 年发现^[1]。紫外线辐射是太阳电磁辐射谱的一部分, 其波长范围为 10-400nm。1932 年召开的第二届国际光学会议^[2]把紫外线分为以下三种: UVA, 波长范围 315-400nm; UVB, 280-315nm; UVC, 100-280nm。另外, 还可以根据紫外线波长与可见光波长的差值把紫外线分类为^[3]: 近紫外(Near Ultraviolet, NUV), 波长范围 300-400nm; 中紫外(Mid Ultraviolet, MUV), 200-300nm; 远紫外(Far Ultraviolet, FUV) 100-200nm; 极远紫外(Extreme Ultraviolet, EUV), 10-100nm。

§1.1.2 紫外线的基本性质

从物理光学的观点看, 紫外线与可见光、红外线都是电磁波, 都具有波动性和粒子性, 遵守光的反射、折射和透射定律, 这是它们的共性。但是由于紫外线的波长更短、能量更大, 又独具特色, 如紫外线的荧光效应、生物效应和光化学效应等。

许多对可见光透明度很好的材料对紫外线的透过率很低, 即它们对紫外线是“不透明的”。例如, 普通窗户玻璃, 对可见光透过率大于 80%, 但对于 350nm 以下波长的紫外线, 则几乎是不透明的。在实际应用中, 可以利用材料的这一种特性来防止短波紫外线对人体的危害。

紫外线的波长较短, 它照射到物体表面时, 更容易被物质吸收, 变成物质的内能, 所以紫外线的穿透能力很弱, 它只作用在物体很薄的表面层。

当紫外线波长小于 200nm 时, 它会被空气中的氧气强烈吸收, 因此波长小于 200nm 的紫外线只能在真空中而不能在空气中传播, 通常称为真空紫外线。

表 1-1 某些透明物质对紫外线的透过率^[1]

| 材料 | 透过率 光波长(nm) | 光透过率(%) | | | | | | |
|------------------|----------------|---------|-----|------|-----|-----|-----|-----|
| | | 400 | 350 | 320 | 310 | 300 | 290 | 200 |
| 普通玻璃(1.5mm 厚) | | 91 | 8 | 0 | 0 | 0 | 0 | 0 |
| 有机玻璃(2mm 厚) | | 94 | 93 | 92 | 90 | 50 | 5 | 0 |
| 一般石英玻璃(2mm 厚) | | 86 | 86 | 85 | 84 | 83 | 83 | 30 |
| 聚氯乙烯(0.1mm 厚) | | 94 | 85 | 81 | 78 | 63 | 0.4 | 0 |
| 聚氟亚乙烯树脂(0.1mm 厚) | | 80 | 80 | 72.5 | 70 | 67 | 65 | 4 |
| 乙烯共聚脂膜(0.1mm 厚) | | 84 | 73 | 5.76 | 53 | 50 | 44 | 0 |

§1.1.3 紫外线的效应

一、紫外线的荧光效应

紫外线的荧光效应是指紫外线照射到某些物质表面时会辐射出紫外线或可见光荧光的现象。

二、紫外线的生物效应

紫外线的生物效应是指当紫外线照射到人体或生物体后使其发生生理变化的现象。紫外线照射人体皮肤会使皮肤黑色素沉着，使皮肤变黑老化，催生皱纹，同时还会增加患上皮肤癌和白内障的机率。世界卫生组织（WHO）指出，有两成白内障病例可能与过度曝晒于紫外线下有关^[4]。

紫外线对人体也有保健作用，例如人体经过特定的紫外线照射后能提高免疫力、皮肤再生能力以及毛发生长速度等。细菌体受紫外线照射之后会死亡，这就是紫外线消毒的工作原理。

不同波长紫外线具有不同的生理作用。图 1-1 为不同波长紫外线的相对杀菌率曲线，可以看到 254-257nm 紫外线的灭菌能力最强^[5]。在非洲和印度等欠发达地区，用紫外线对受污染的河水灭菌是解决当地饮用水缺乏问题的既经济又行之有效的方法；空气中的氧分子吸收波长小于 200nm 的紫外线后，氧分子间的化学键被打断分解为氧原子，氧原子吸收紫外线后又与空气中的其它氧分子化合形成臭氧，臭氧有强烈的氧化和灭菌作用。

三、紫外线的光化学效应

紫外线照射某些物质时会引起这些物质产生光化学反应，如胶卷的感光、植物的光合作用、有机物的合成和分解、半导体器件工艺过程中的光刻曝光等。

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